

L Number	Hits	Search Text	DB	Time stamp
1	27606	((low near10 dielectric) (organo near3 silic\$5 near3 glass))	USPAT; US-PGPUB	2003/04/02 15:57
2	1300	((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))	USPAT; US-PGPUB	2003/04/02 15:51
3	2539	((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))	USPAT; US-PGPUB	2003/04/02 15:52
4	3454	((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma)))	USPAT; US-PGPUB	2003/04/02 15:20
5	2106	((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))	USPAT; US-PGPUB	2003/04/02 15:58
6	1848	((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))) and (via trench hole open\$4)	USPAT; US-PGPUB	2003/04/02 15:23
7	361	((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))) and (via trench hole open\$4)) and (wet near8 (treat\$3 etch\$3 clean\$3))	USPAT; US-PGPUB	2003/04/02 15:53
8	206	((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))) and (via trench hole open\$4)) and (wet near8 (treat\$3 etch\$3 clean\$3))) and (HF (hydrogen near3 fluoride) (hydro near3 fluoric near3 acid) (sulfuric near3 acid) ("H.sub.2" adj "SO.sub.4") ((citric acetic oxallic) near5 acid))	USPAT; US-PGPUB	2003/04/02 15:55
9	17236	((low near10 dielectric) (organo near3 silic\$5 near3 glass))	EPO; JPO; DERWENT; IBM_TDB	2003/04/02 15:51
10	123	((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))	EPO; JPO; DERWENT; IBM_TDB	2003/04/02 15:52
11	123	((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))	EPO; JPO; DERWENT; IBM_TDB	2003/04/02 15:52
12	235	((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma)))	EPO; JPO; DERWENT; IBM_TDB	2003/04/02 15:52
13	34	((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))	EPO; JPO; DERWENT; IBM_TDB	2003/04/02 15:52

14	2	(((((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))) and (wet near8 (treat\$3 etch\$3 clean\$3))	EPO; JPO; DERWENT; IBM_TDB	2003/04/02 15:53
15	2	(((((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))) and (HF (hydrogen near3 fluoride) (hydro near3 fluoric near3 acid) (sulfuric near3 acid) ("H.sub.2" adj "SO.sub4") ((citric acetic oxallic) near5 acid))	EPO; JPO; DERWENT; IBM_TDB	2003/04/02 15:58
16	4772	(damascene (dual near3 damascene))	USPAT; US-PGPUB	2003/04/02 15:57
17	779	((damascene (dual near3 damascene))) and (((low near10 dielectric) (organo near3 silic\$5 near3 glass)) same plasma)	USPAT; US-PGPUB	2003/04/02 15:58
18	543	((damascene (dual near3 damascene))) and (((low near10 dielectric) (organo near3 silic\$5 near3 glass)) same plasma)) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))	USPAT; US-PGPUB	2003/04/02 15:58
19	162	((damascene (dual near3 damascene))) and (((low near10 dielectric) (organo near3 silic\$5 near3 glass)) same plasma)) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))) and (HF (hydrogen near3 fluoride) (hydro near3 fluoric near3 acid) (sulfuric near3 acid) ("H.sub.2" adj "SO.sub4") ((citric acetic oxallic) near5 acid))	USPAT; US-PGPUB	2003/04/02 15:59